

Sejong

Scientific

Instruments

Laser Direct Writer UVW02

Easy to use
Reasonable Price
Compact Design

Product Information

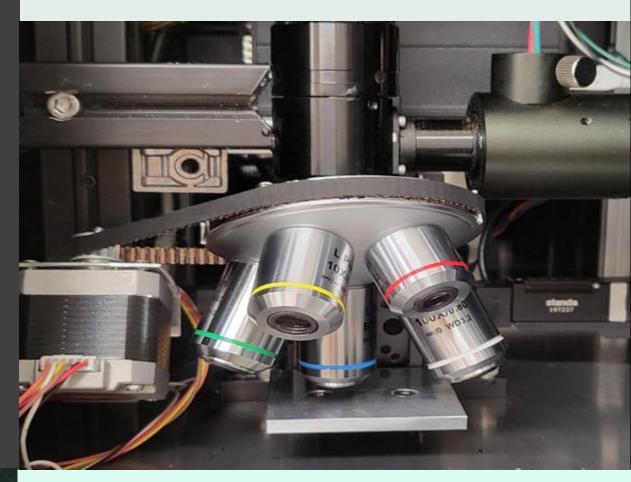
- Photolithography for various devices
 - Manufacturing unit devices for research
 - Semiconductor devices, solar devices,
 - Microfluidic channel, lab-on-a-chip
- Optical microscope + 405 nm laser focus
- Objectives: 5x, 10x, 20x, 50x, 100x
- automatic switching
- Laser focus, sample focus switchable
- Autofocus function included as standard

Performance

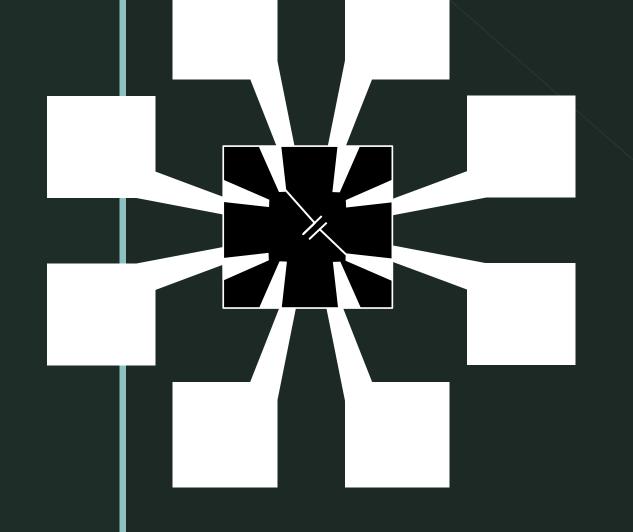
- ➢ Minimum linewidth: ~1 µm
- Sample stage resolution: 0.125 μm
- Scannable range: up to 25 mm x 25 mm

Features

- Affordable price for small-scale research
- Open design specialized research through modification
- Compact design (height: 47cm), USB connection → Glove box insertable



Usage



- Various semiconductor devices
- Production of solar energy devices
- Microfluidics, Lab-on-a-chip

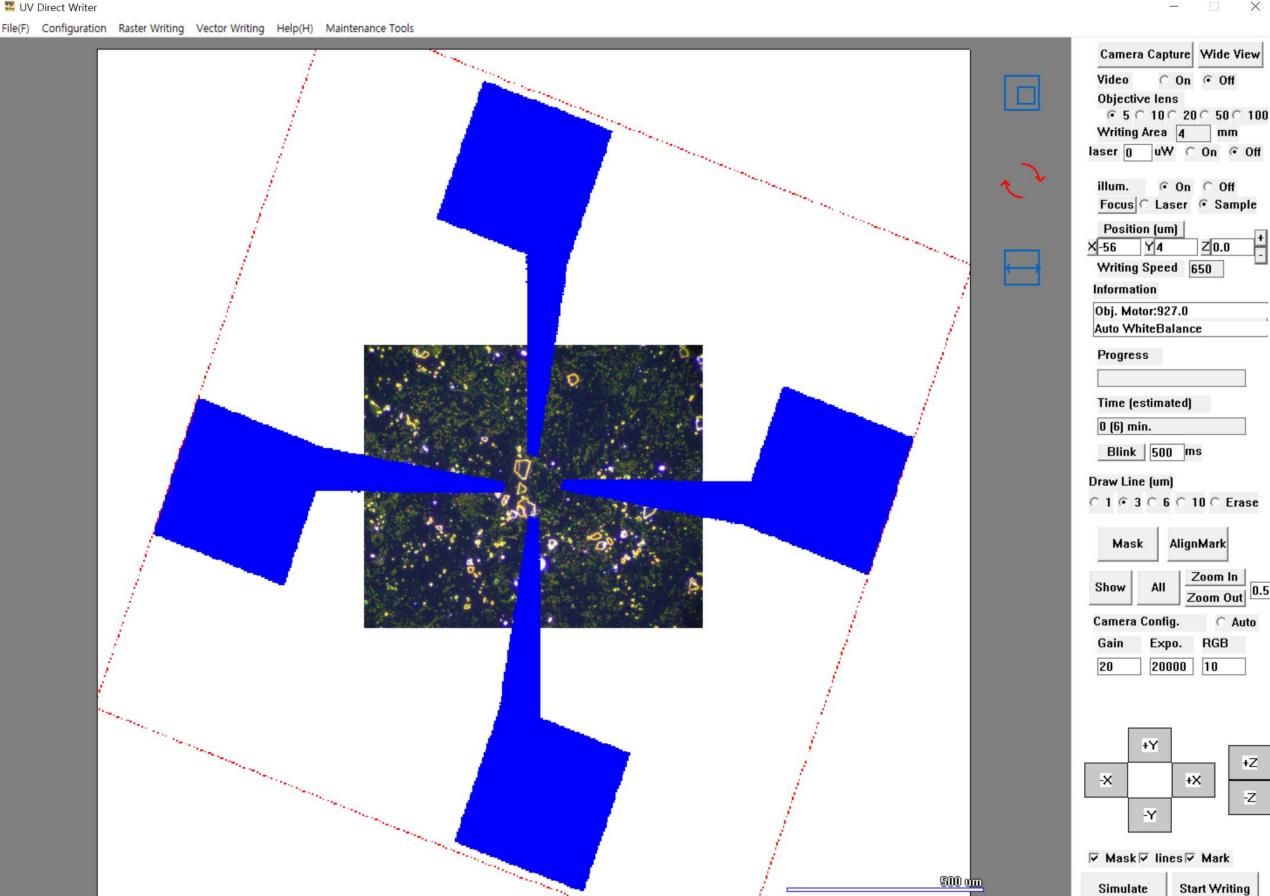
convenience features

- ✓ Load pattern image file
- ✓ Draw lines directly with the mouse
- ✓ Auto-focusing!
- ✓ fine patterns and contact pads at once
- Keyboard operation \rightarrow position adjustment
- ✓ Mouse operation → move to a specific location on the sample

Features:

Micro photolithography equipment Minimum line width: <1 um (depending on PR thickness) objective lens: 5x, 10x, 20x, 50x, 100x Focus plane automatically adjusted by selecting objective lens Laser diode: 405 nm, 50 mW Laser intensity adjustable (to 500 uW @ 100x objective lens) Writing scan speed adjustable While observing confocal image, lines can be drawn by user Software zoom-in and zoom-out for line drawing 2 writing mode: Raster writing and Vector writing Raster writing: filling area after opening external image file Thick (thin) pen writing with high (lower) laser intensity Vector writing: line pattern writing drawn by mouse clicking

Stand alone equipment with USB interface from PC sample mount: 5 cm x 5 cm flat stage, large wafer available scanner: motorized XYZ stage Wide view area: from 5x objective lens Precise aligning: from 100x objective lens 9 image patched image automatic focusing Dimension (including chassis): 28 x 36 x 46 cm³ User interface for real-time monitoring while writing Mouse control of Mask image: moving, stretching, rotating on camera image



Best cost-effective research unit device processing equipment

- ◆ Draw the pattern you want freely without a metal mask..
- Existing photolithography resist is used as is.
- ✤ It can be used in small laboratories to manufacture various device electrodes at an affordable price.
- ✤ GPIB and USB interface functions are provided as standard for connecting general external devices.
- ✤ We provide technical support for additional interfaces and active assistance with software changes.
- Compact design (height: 44cm), a miniaturized design with a single USB connection, allows for gas atmosphere control when installed in a glove box.

Aim for independence in research equipment.!!!

- * We use standardized parts that allow users to freely modify them for original research.
- ✤ It was created on an open-source basis so that it can be modified and conduct specialized research.
- We provide a software library so that customers can change the program as they wish.

We change the program (paid service) to reflect the needs of individual users. ↔ We guarantee 1 year of free A/S and support software updates according to PC changes for 10 years.



Laser Direct Writer (UVW02) (Inc.) Sejong Scientific Instruments